

High-speed Vertical Positioning Stage with Integrated Dual-sensor Arrangement

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Abstract

This article presents a novel vertical positioning stage with a dual-sensor arrangement suitable for scanning probe microscopy. The stage has a travel range of 8.4 μm and a first resonance frequency of 24 kHz in the direction of travel. The sensor arrangement consists of an integrated piezoelectric force sensor and laminated piezoresistive strain sensor. The piezoelectric force sensor exhibits extremely low noise and introduces a zero into the dynamics which allows the use of integral force feedback. This control method provides excellent damping performance and guaranteed stability. The piezoresistive sensor is used for tracking control with an analog PI controller which is shown to be an approximate inverse of the damped system. The resulting closed-loop system has a bandwidth is 11.4 kHz and 6σ -resolution of 3.6 nm, which is ideal for nanopositioning and atomic force microscopy (AFM) applications. The proposed vertical stage is used to replace the vertical axis of a commercial AFM. Scans are performed in constant-force contact mode with a tip velocity of 0.2 mm/s, 1 mm/s and 2 mm/s. The recorded images contain negligible artefacts due to insufficient vertical bandwidth.

Keywords: Piezoresistive, strain sensor, piezoelectric, force sensor, nanopositioning, control, high-speed, AFM

1. Introduction

Compact, high-bandwidth nanopositioning systems have been employed in a wide range of applications, including precision alignment of fiber optics [1], scanning probe microscopy [2–5], beam steering systems [6] and cavity ring-down spectroscopy in optical applications [7, 8]. Piezoelectric stack actuators are used in these precision systems due to the high force and stiffness. However, piezoelectric stack actuators exhibit hysteresis over a large range and creep at low frequencies. These nonlinearities can cause tracking errors greater than 20%.

Many forms of feedback and feedforward control have been applied to eliminate vibration, hysteresis and creep [9–11]. Inversion-based feedforward techniques [11–13] can be used to suppress the sharp resonance behavior and improve the tracking performance of nanopositioning systems without the need of a sensor. However, the main disadvantage of feedforward control is the need for an accurate model and a stable resonance frequency. A nonlinear model, which may be

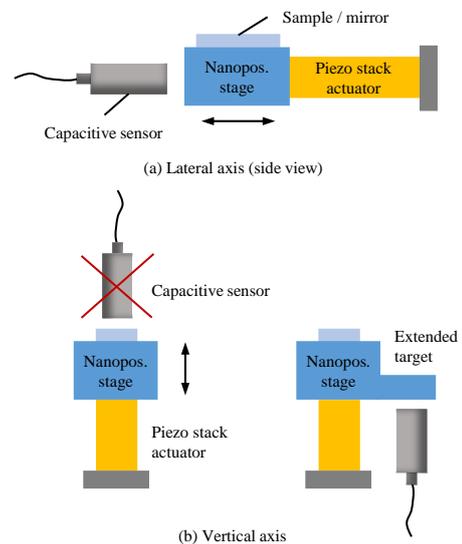


Figure 1: Installation of a capacitive sensor on the lateral and vertical axes of a nanopositioner.

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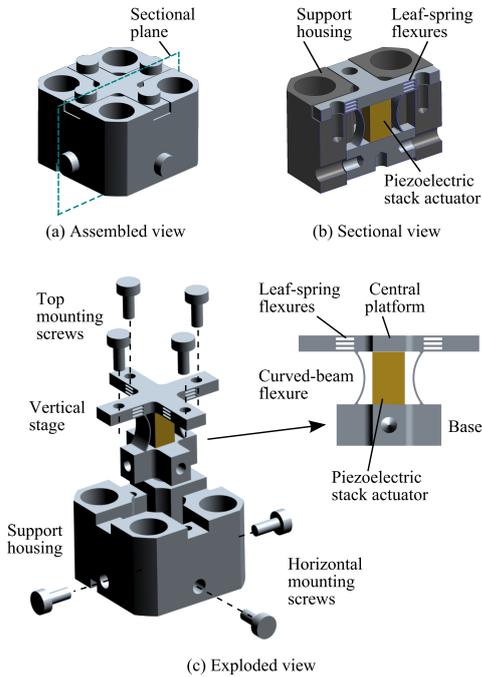


Figure 2: High-speed vertical stage. (a) Assembly view showing the vertical stage being mounted to its support housing. (b) Sectional view showing the vertical stage, support housing and piezoelectric stack actuator. (c) Exploded view of the vertical stage.

computationally demanding to invert, is also required for hysteresis and creep compensation.

Sensor-based feedback control is one of the most commonly used techniques for controlling piezoelectric systems [11, 13–16]. This approach is simple, insensitive to modeling error, and effectively reduces non-linearity. Damping controllers, such as integral resonant control [17–19], positive position feedback [20–23], resonant control [24] and polynomial-based controller [25] have been used to suppress resonances and reduce the bandwidth limitations imposed by mechanical resonances. However, when a damped system is included in an integral tracking loop, the closed-loop system is still limited by a low gain margin [26]. Moreover, the wide bandwidth of a damping controller can introduce sensor-induced positioning noise to the system.

Capacitive sensors are among the most popular sensors used in nanopositioning systems owing to their low noise, high resolution and relatively low cost [27]. They can be easily installed in the lateral axis of nanopositioning systems as shown in Fig. 1(a). However, for the vertical axis of a compact nanopositioner, the installation of the sensor becomes challenging. As shown in Fig. 1(b), additional mass on the moving platform may

be needed to serve as a target for the sensor, which increases the physical size and reduces the resonance frequency.

In this work, a dual-sensor system is proposed for controlling vibration and nonlinearity in a piezoelectric driven, high-speed vertical stage. The technique utilizes a piezoelectric force sensor and a piezoresistive strain sensor to estimate displacement. The two sensors are bonded to the piezoelectric stack actuator directly which allows for an extremely compact design. The piezoelectric force sensor provides a wide bandwidth with low noise at high frequencies [28, 29]. Although piezoelectric force sensors have excellent AC properties, the sensitivity is temperature dependent and they are not suitable for low-frequency measurements due to the capacitive source impedance which imposes a first-order high-pass response. To overcome these limitations, a piezoresistive strain sensor is used for tracking control and to augment the force sensor at frequencies below 10 Hz. Piezoresistive strain sensors can be directly bonded to a stack actuator without affecting the dynamic performance. The sensitivity of piezoresistive sensors is typically two orders of magnitude greater than metal foil strain sensors so sub-nanometer resolution can be achieved at kHz bandwidths [27].

The performance of the proposed vertical system is demonstrated on a commercial AFM where the vertical axis of the AFM is replaced by the high-speed vertical stage. Many common modes of scanning probe microscopy (SPM), such as constant-force AFM and constant-current scanning tunneling microscopy, require a vertical feedback system to regulate the interaction force between tip and sample. A major speed limitation in these modes is the vertical feedback bandwidth [2, 3, 30–32]. During a high-speed scan, an AFM system with a low vertical feedback bandwidth is unable to track sharp features in a sample topography. This leads to the "smudging" feature edges in the image [13, 30]. The most commonly used vertical feedback controller in an AFM is an integral controller. The vertical bandwidth can therefore be estimated as ω_n/P , where ω_n is the resonance frequency and P is the peak magnitude [33]. By increasing the resonance frequency of the vertical stage, and actively damping the resonance using force-feedback, the maximum vertical feedback bandwidth can be improved significantly.

The remainder of the paper proceeds as follows. Sec. 2 presents the design of the vertical stage and the preload mechanism. This section also discusses the design of the actuator and sensor arrangement. Feedback control strategies using the dual-sensor arrangement are presented in Sec. 3. Experimental results can be found

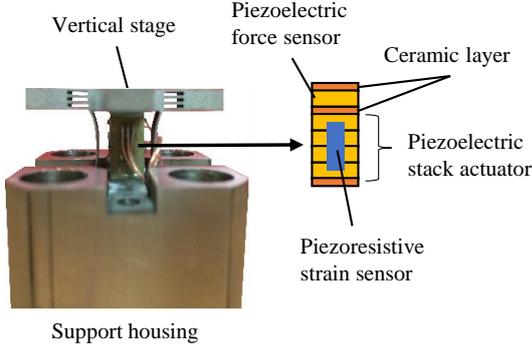


Figure 3: Piezoelectric stack actuator with force and piezoresistive strain sensors.

in Sec. 4. Sec. 5 reports the position noise of the sensors and closed-loop system. The vertical system is then used for Atomic Force Microscopy (AFM) in Sec.6. The article is concluded in Sec. 7.

2. High-speed Vertical Stage Design

Fig. 2 illustrates the proposed high-speed vertical stage which consists of four sets of leaf-spring flexures arranged orthogonally. These flexures allow the central platform to move vertically while simultaneously restraining the lateral motion. A 7 mm×7 mm×11.5 mm piezoelectric stack actuator is used to deform the flexures elastically and to drive the central platform.

2.1. Actuator and Sensors

The piezoelectric stack actuator is constructed from four 2-mm plate stacks (NOLIAC NAC2021) bonded in series to a 2-mm NAC2021 force sensor as shown in Fig. 3. A 0.5-mm ceramic plate is used to separate the sensor and actuator in order to minimize Poisson coupling from the actuator to sensor. Two more ceramic plates are glued to each end of the actuator respectively to electrically isolate the actuator from the nanopositioner. The piezoresistive strain sensor is a Micron Instruments SSGH-060-033-1000PB half-bridge which is glued to the side of the actuator for displacement measurement.

2.2. Preloading and installation of piezoelectric stack actuator

To prevent damage due to tensile stress, a sufficient preload is required to compensate for inertial forces. Many high-speed nanopositioner systems uses flexures to preload piezoelectric stack actuators [3, 14, 31, 34]. These flexures are also used to provide the requisite

stiffness for high-speed operation. However, due to the high stiffness, it is difficult to achieve a measured preload during installation. For instance, to deform a group of flexures with a combined stiffness of 10 N/μm [14, 34] by 0.3 mm, a pulling force of 3000 N is required. To provide this pulling force, a specially designed pulley system or a high-force preloading tool may be needed. The stiffness of flexures may be reduced to simplify the installation process but this degrades the dynamic performance.

The proposed vertical stage includes two curved flexures shown in Fig. 2 which simplify the actuator installation and preloading. The low stiffness of the curved flexures permits installation of the actuator with tens of Newtons of force. This preload force can be practically applied using precision screws. Details of the curved flexure design and the preloading procedure can be found in [35].

3. Feedback Control Strategy

Due to the capacitive source impedance of the piezoelectric force sensor, the dynamics resemble a high-pass filter with a cut-off frequency of $1/RC_p$, where R is the input impedance of the instrumentation and C_p is the capacitance of the sensor. In the experimental setup, the capacitance and resistance are 158 nF and 100 MΩ which result in a high-pass cut-off frequency of 0.01 Hz.

The vertical stage is considered to be a single-input two-output (SITO) system described by

$$\begin{bmatrix} d \\ f \end{bmatrix} = \begin{bmatrix} G_{da} \\ G_{fa} \end{bmatrix} V_a, \quad (1)$$

where V_a is the applied input voltage, d is the piezoresistive strain sensor measurement, and f is the piezoelectric force sensor measurement. The sensitivity of the piezoresistive strain sensor was measured to be 42 mV/μm, which was approximately 5% of the force sensor. For simplicity, the strain sensor signal was amplified so that the sensitivity was equal to the force sensor, that is 1.594 V/μm.

The transfer functions from V_a to d and f were identified to be

$$G_{da} = \frac{2.48 \times 10^{10}}{s^2 + 22060s + 2.483 \times 10^{10}} \quad (2)$$

$$G_{fa} = \frac{2.789s^2 + 5250s + 2.048 \times 10^{10}}{s^2 + 22060s + 2.483 \times 10^{10}}. \quad (3)$$

3.1. Integral Force Feedback

To suppress the resonance of the vertical stage, an integral force feedback (IFF) controller is implemented as

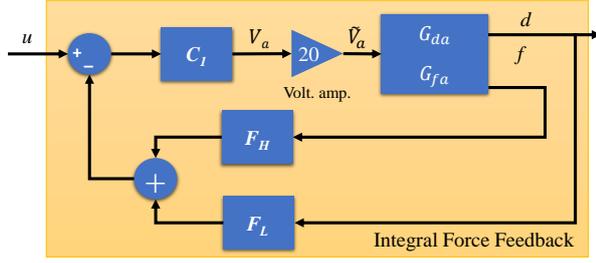


Figure 4: The integral force feedback damping control loop.

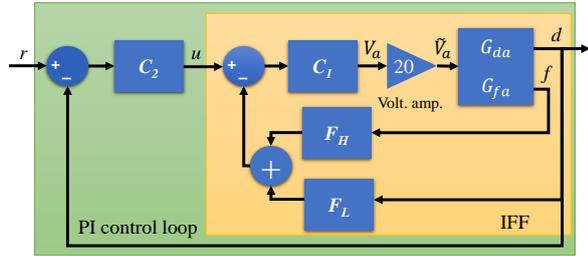


Figure 5: The reference tracking and damping control loops where C_1 is the integral force feedback controller and C_2 is the PI controller.

shown in Fig. 4. A pair of complementary filters F_L and F_H are used to substitute f for d at frequencies below the cut-off frequency f_c , chosen to be 10 Hz. F_L and F_H are first-order filters with transfer functions

$$F_L = \frac{2\pi f_c}{s + 2\pi f_c} \quad \text{and} \quad F_H = \frac{s}{s + 2\pi f_c}. \quad (4)$$

The IFF loop consists of the plant G_{fa} and an integrator $C_1(s) = \alpha/s$ [26]. The closed-loop response of the damping loop from u to d is

$$G_{du} = \frac{C_1 G_{da}}{1 + C_1 G_{fa}}. \quad (5)$$

Due to the force sensor, the transfer function G_{fa} exhibits zero-pole interlacing pattern where the phase response lies between 0° and 180° . Such systems are known as negative imaginary systems and have guaranteed stability with an integral controller [36]. Using the root-locus method, an integral gain of $\alpha = 14000$ was found to achieve optimal damping.

3.2. Tracking Control

An outer tracking control loop is implemented using the piezoresistive strain sensor as illustrated in Fig. 5. The damping control loop G_{du} features an additional real axis pole introduced by the IFF controller [37]. This

additional pole can be approximately inverted by placing a zero at a similar frequency [37]. Since the desired loop gain is integral action, a suitable controller is

$$C_2(s) = \frac{k_i(s + w_z)}{s w_z}, \quad (6)$$

where k_i is an integral gain, and w_z is the frequency of the additional pole which can be found experimentally, by examining the pole-zero map of G_{du} or by the Cardano's method [37]. C_2 is a PI controller with a parameterized zero location. In the experimental setup, w_z was found to be 11800 rad/s. A tracking controller gain of $k_i = 25000$ was chosen which results in a gain margin of 7.2 dB and phase margin of 72° .

4. Experimental results

A Polytec PSV-300 laser scanning vibrometer was used to measure the open- and closed-loop frequency response of system. The open-loop frequency responses were measured from the applied voltage V_a to the displacement d . The damping loop responses (IFF) were measured from the signal u to d , and the closed-loop tracking responses (IFF+PI) were measured from r to d . Results measured by the laser and the strain sensor are plotted in Figs. 6 and 7 respectively. With the implementation of the IFF and PI controllers, the magnitude of the first resonance mode is suppressed by 16 dB. The 3-dB bandwidth of the closed-loop system is 11.4 kHz which is approximately 50% of the first resonance frequency. This is an excellent result given that the controller is second order and implemented by analog circuit.

To evaluate the effect of hysteresis, the vertical stage was driven at full range ($8.4 \mu\text{m}$) with a sinusoidal input at 10 Hz. The open- and closed-loop hysteresis plots are shown in Fig. 8. The hysteresis is observed to be eliminated at this frequency.

5. Noise and resolution estimation

In this work, the foremost sources of noise are the strain and force sensor. The noise density function of the piezoresistive strain and piezoelectric force sensors are plotted in Fig. 9. The piezoelectric force sensor exhibits low noise at high frequencies but is dominated by integrated current noise from the instrumentation at low frequencies, which results in $1/f^2$ characteristic. The piezoresistive strain sensor has a higher noise density of $1.5 \text{ pm}/\sqrt{\text{Hz}}$. However, at low-frequencies, the piezoresistive sensor exhibits a $1/f$ characteristic which is due

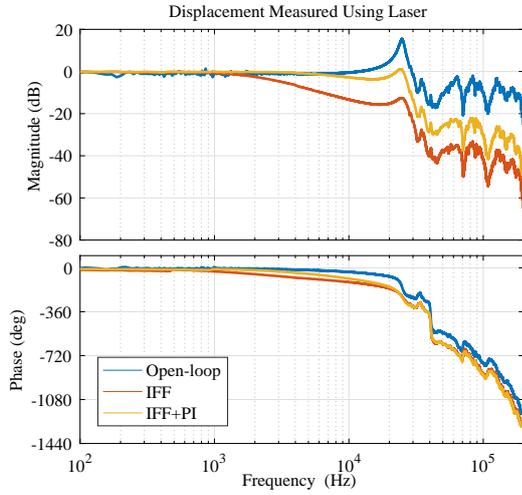


Figure 6: Normalized frequency responses of the vertical stage measured using a laser vibrometer.

to semiconductor noise. This $1/f$ characteristic results in significantly less DC to 10-Hz noise compared to the $1/f^2$ characteristic of the force sensor.

The total closed-loop positioning noise is estimated using the time-domain applied voltage method described in reference [38]. In this method, the total positioning noise can be estimated by measuring the applied voltage \tilde{V}_a to the plant in closed-loop (see Fig. 5), and post-filtering it by the plant dynamics. A 10 s period of the applied voltage was recorded at 512 kHz. An SR560 low-noise preamplifier was used to amplify the AC component of the signal by 20 and to filter the signal with a first-order high-pass filter at 0.016 Hz and second-order low-pass filter at 30 kHz. The recorded signal \tilde{V}_a was then filtered by the model G_{da} using `lsim` in Matlab.

The closed-loop position noise and its approximately Gaussian distribution are plotted in Figs. 10 and 11. The position noise has an RMS value of 0.6 nm and a 6σ -resolution of 3.6 nm. This resolution can be compared to that achievable with a state of the art MicroSense 6810 capacitive sensor with a noise density of $10 \text{ pm}/\sqrt{\text{Hz}}$ and a $1/f$ noise corner frequency of 100 Hz. In ideal conditions (ignoring 50 Hz noise), the capacitive sensor would provide a predicted closed-loop 6σ -resolution of approximately 2.6 nm, which is comparable to the resolution achieved with the proposed

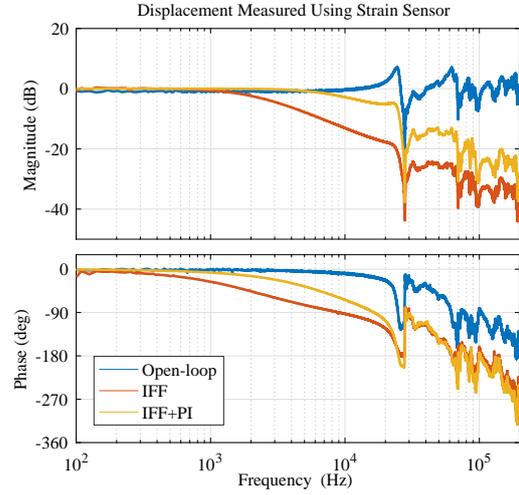


Figure 7: Normalized frequency responses of the vertical stage measured using piezoresistive strain sensor.

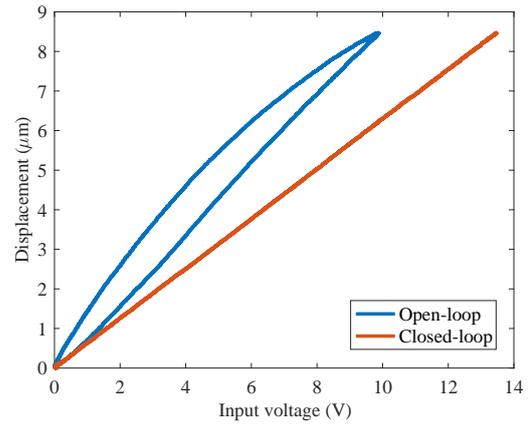


Figure 8: Hysteresis plots of the system in open- and closed-loop.

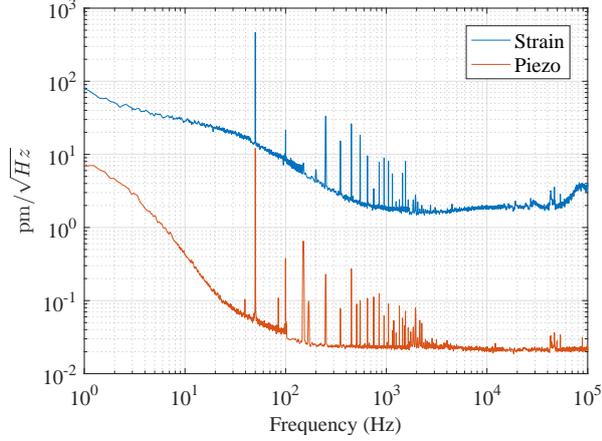


Figure 9: Noise density function of the piezoresistive strain sensor, piezoelectric force sensor and the closed-loop system.

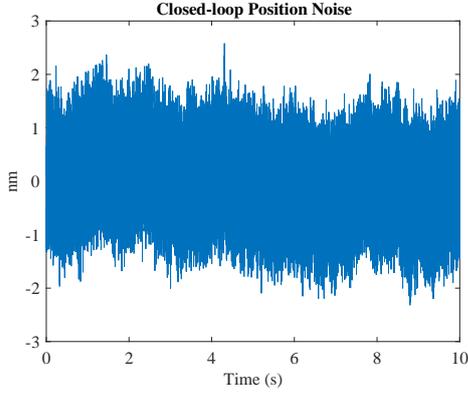


Figure 10: Closed-loop position noise measured in time-domain.

sensor arrangement.

$$6\sigma\text{-resolution} = 6\sqrt{A} \sqrt{f_{nc} \ln \frac{f_h}{f_l} + k_e f_h} \quad (7)$$

where A is the noise density, f_{nc} is the $1/f$ noise corner frequency, f_l and f_h are the lower and upper bounds of the bandwidth of interest, and $k_e = 1.57$ is a correction factor that accounts for the finite roll-off of the system.

6. AFM imaging

In this section, the performance of the proposed closed-loop vertical system is evaluated for AFM applications. The AFM experiments were conducted in constant-force contact-mode with a HS-500MG sample grating which has a rectangular profile of $5 \mu\text{m}$ period and 500 nm height. A BudgetSensors Tap190Al-G cantilever with a resonance frequency of 190 kHz was used

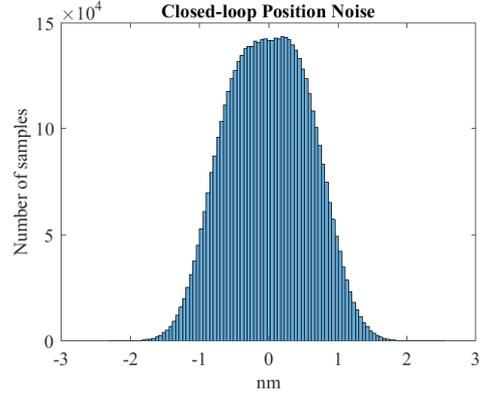


Figure 11: Distribution of the closed-loop position noise.

to probe the sample. The contact force was regulated at 35 nN while scanning a sample area of $100 \mu\text{m} \times 100 \mu\text{m}$ with 256×256 pixels resolution.

Firstly, the Nanosurf AFM which has a closed-loop vertical bandwidth of 45 Hz is used to interrogate the sample at 1 Hz line rate. Fig. 13 shows the resulting topography image and the single-line profile of the grating. The shape and height of the profile are heavily distorted by the limited bandwidth of the vertical feedback loop. In constant-force imaging modes, the vertical feedback controller regulates the contact force in response to the topography signal which enters the loop as an input disturbance. For a $100 \mu\text{m} \times 100 \mu\text{m}$ scan area at 1 Hz line rate, the tip velocity is $v_{tip} = 200 \mu\text{m/s}$. Assuming the sample has a sinusoidal profile with periodicity λ , the required feedback bandwidth is [4]

$$f_B \geq \frac{v_{tip}}{\lambda}. \quad (8)$$

For $\lambda = 5 \mu\text{m}$, f_B is required to be at least 40 Hz . Note that the above estimation is for a sinusoidal profile, significantly higher bandwidths are required to track topographies with step changes.

The same experiments were repeated where the vertical axis of the AFM was replaced by the proposed vertical stage, as shown in Fig. 12. C_3 is an integral controller used to regulate the contact force at 35 nN . The integral gain was set to 26000 . As a result, the closed-loop vertical bandwidth of the AFM was measured to be 9 kHz . The AFM images obtained at 1 Hz , 5 Hz and 10 Hz line rates are plotted in Fig. 14. The corresponding tip velocities were 0.2 mm/s , 1 mm/s and 2 mm/s respectively. No imaging artefacts due to the vertical bandwidth can be observed. However, at the higher scan-rates, distortion due to the dynamics of the lateral axes can be observed. Oscillations appear in the

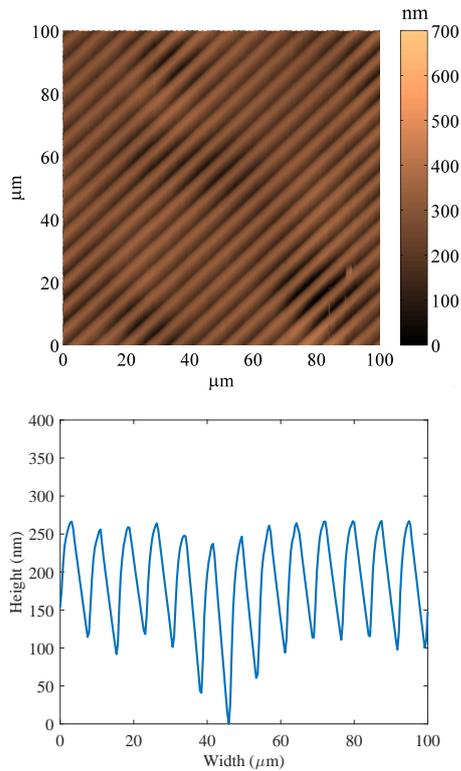


Figure 13: The topography (top) and profile (bottom) of the sample obtained using the commercial AFM at 1 Hz scan rate.

recorded images when the lateral scan rate is increased to 5 Hz and 10 Hz respectively. These oscillations are more noticeable at the start of each scan line (left side of the image) due to the fast dynamics content of the lateral triangular reference. Similar vibration-induced artifacts have been described in [13, 14, 18, 34].

To illustrate the benefits of actively damping the vertical stage in AFM applications, Fig. 15 compares the simulated vertical feedback bandwidth with and without active damping. In both cases, the integral tracking controller (C_3) was tuned to provide a 10 dB gain-margin. The system without active damping has a 3-dB bandwidth of 330 Hz, while the system with active damping has a bandwidth of 9 kHz. Therefore, if the vertical stage has a significant resonance peak, active damping can significantly increase the performance while retaining a simple vertical feedback controller. It is advantageous to retain a simple vertical feedback controller as this is regularly retuned after a change of imaging mode, sample, or cantilever.

7. Conclusions

This article presents a high-speed vertical stage with an integrated dual-sensor arrangement for vibration and tracking control. The dual-sensor arrangement of a piezoelectric force sensor and piezoresistive strain sensor offers a compact alternative to capacitive and optical sensors. The integral force feedback damping controller and PI tracking controller provided a closed-loop bandwidth of 11.4 kHz, which is approximately 50% of the first resonance frequency. The closed-loop 6σ positioning resolution was measured to be 3.6 nm, which is comparable to that achievable with a high-performance capacitive sensor.

When the proposed stage was used to replace the vertical axis of a commercial AFM, the closed-loop vertical feedback bandwidth was increased from 43 Hz to 9 kHz. AFM images recorded at velocities of 0.2 mm/s, 1 mm/s and 2 mm/s demonstrate the elimination of imaging artefacts associated with insufficient vertical feedback bandwidth.

8. Acknowledgments

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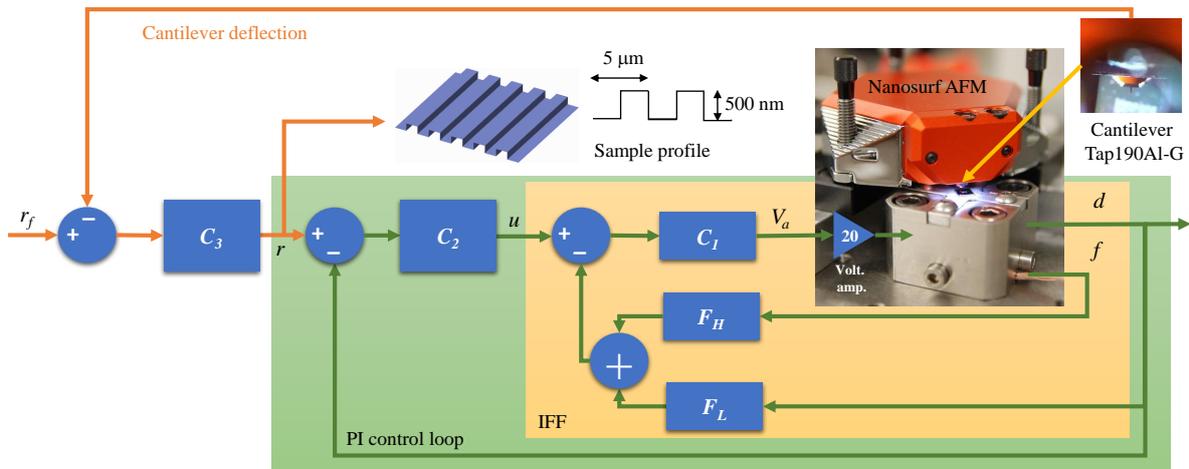
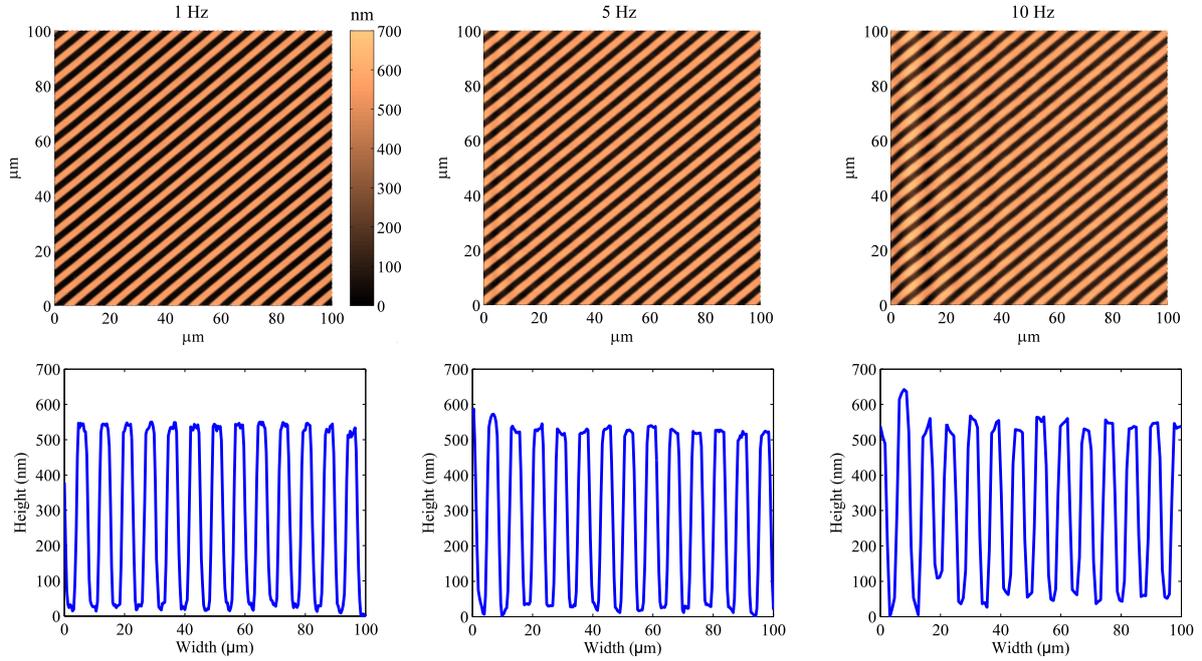


Figure 12: Experimental setup for performing constant-force contact-mode AFM. The high-speed vertical stage is mounted under the Nanosurf AFM. C_3 is an integral controller with a gain of 26000. r_f is the force set-point of 35 nN.

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(a) Recorded sample topography with line rates increasing from 1 Hz to 10 Hz



(b) Recorded contact force error with line rates increasing from 1 Hz to 10 Hz

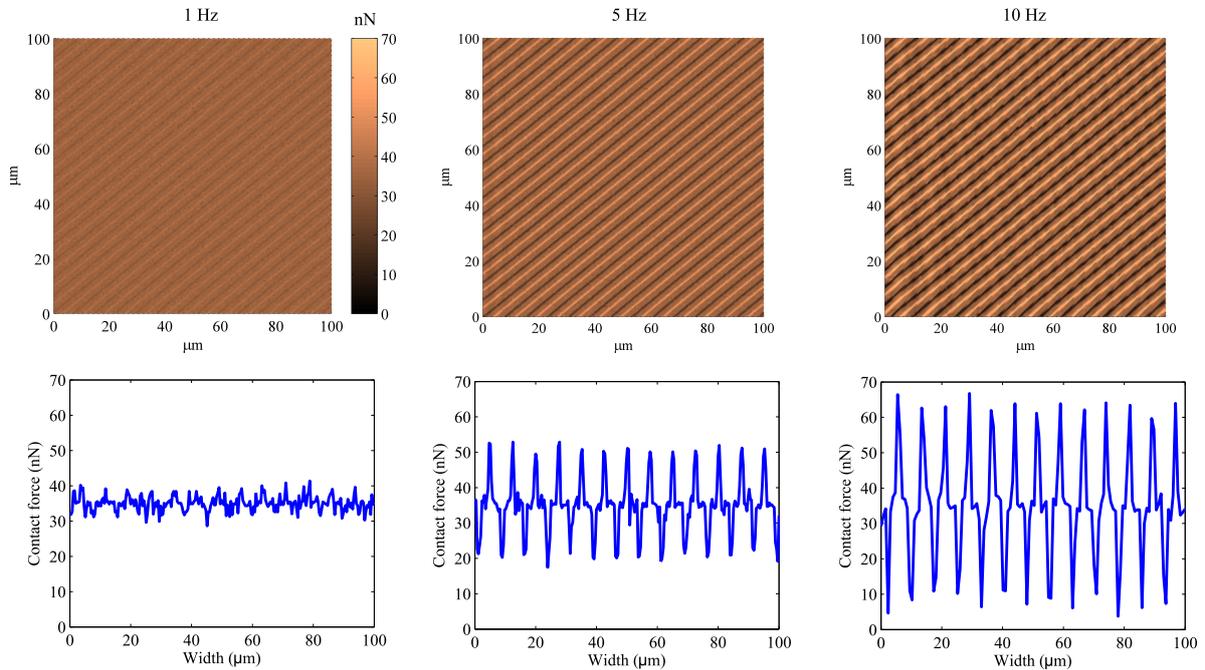


Figure 14: AFM images and contact force errors obtained using the proposed high-speed vertical stage for line rates of 1 Hz, 5 Hz and 10 Hz. The quality of these images are much superior compared to that of the commercial AFM in Fig. 13.

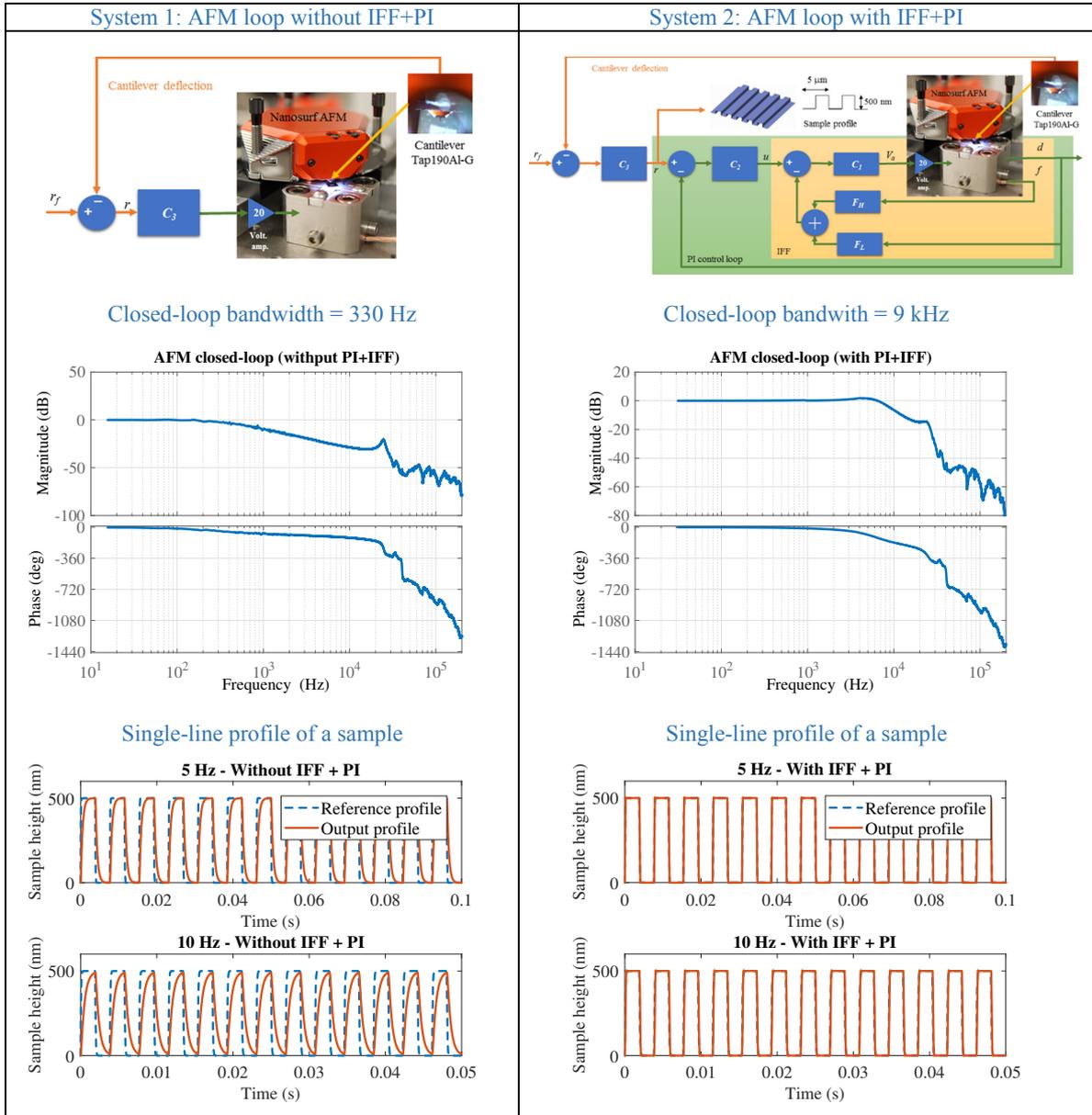


Figure 15: Tracking performances of an AFM closed-loop system without the IFF+PI inner loop (left column); and with the IFF+PI inner loop (right column). First row: System block diagram. Middle row: Frequency response of each system, indicating their closed-loop bandwidths. Last row: Tracking of a single-line profile of a sample with rectangular features at 5Hz and 10 Hz line rates.

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